

Special Issue

Low-Temperature Plasma: Advancements and Applications

Message from the Guest Editor

Low-temperature plasma is a unique state of matter in which most particles are neutral or weakly ionized, making it an attractive candidate for a wide range of applications. Our daily lives are increasingly reliant on low-temperature plasma. For example, the production and testing of computer chips require plasma, and materials used in artificial joints and dental implants also need plasma treatment to enhance their biocompatibility. As research advances, existing low-temperature plasma applications are being improved while new areas of usage, such as nitrogen fixation, are emerging. This has led to numerous international conferences dedicated to low-temperature plasma, including the Gaseous Electronics Conference, IEEE International Conference on Plasma Science (ICOPS), International Symposium on High Pressure, Low-Temperature Plasma Chemistry (HAKONE), and the International Symposium on Plasma Chemistry. Low-temperature plasma is a unique state of matter in which most particles are neutral or weakly ionized, making it an attractive candidate for a wide range of applications. Our daily lives are increasingly reliant on low-temperature plasma.

Guest Editor

Prof. Dr. Xinpei Lu

School of Electrical and Electronic Engineering, Huazhong University of Science And Technology, Wuhan 430074, China

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Applied Sciences
Editorial Office
MDPI, Grosspeteranlage 5
4052 Basel, Switzerland
Tel: +41 61 683 77 34
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Editor-in-Chief

Prof. Dr. Giulio Nicola Cerullo
Dipartimento di Fisica, Politecnico di Milano, Piazza L. da Vinci 32,
20133 Milano, Italy

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